

INSTALLATION FOR TREATING SEMICONDUCTOR WAFERS**ABSTRACT**

An improved installation for treating semiconductor wafers is described. The installation includes a tank adapted to contain a treatment bath and equipped with a wafer-holding device capable of receiving at least one wafer of a first size, and a gripping element for grasping each wafer of the first size and for placing it into and removing it from the tank. Also included is a support adapter for receiving wafers of a second size smaller than the first size, the support adapter having a structure that permits it to be grasped directly by the gripping element and held by the wafer-holding device. At least one rotation-blocking element prevents the support adapter from rotating relative to the wafer-holding device when the support adapter is positioned in the wafer-holding device.

NY:804709.1